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(54) ION BEAM IRRADIATION DEVICE

(57)Abstract:

PURPOSE: To irradiate a broad region without dropping accuracy by laying plural ion beam generation means and irradiating a desired region of a sample while controlling each ion beam through a deflection means.

CONSTITUTION: Plural ion beam guns 3aW3c put side by side in a row, a power source 2 and an outgoing electrode 4 are housed in the ion beam generation part 1 of an ion beam irradiation device. And only the parallel components are taken out from individual ion beams 5aW5c through collimators 6 while being focused by electrostatic lenses 7, blanked by deflectors 8 for blanking and further deflected by deflectors 9 for scanning the desired regions of a sample 10 traveling in the arrow direction. Accordingly, as plural ion beams are used, pattern accuracy is not dropped thus allowing ion beams to irradiate a broad region and yet with simple constitution.

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